

Attenuation type phase shifting mask - has drive transparent part surrounding second transparent part and auxiliary pattern formed on first transparent parts

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Patent Family

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DE 19510564	A1	19951026	DE 1010564	A	19950323	199548	B
JP 7281413	A	19951027	JP 9466934	A	19940405	199601	
US 6048647	A	20000411	US 95395004	A	19950227	200025	
			US 97798007	A	19970212		
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Patent Details

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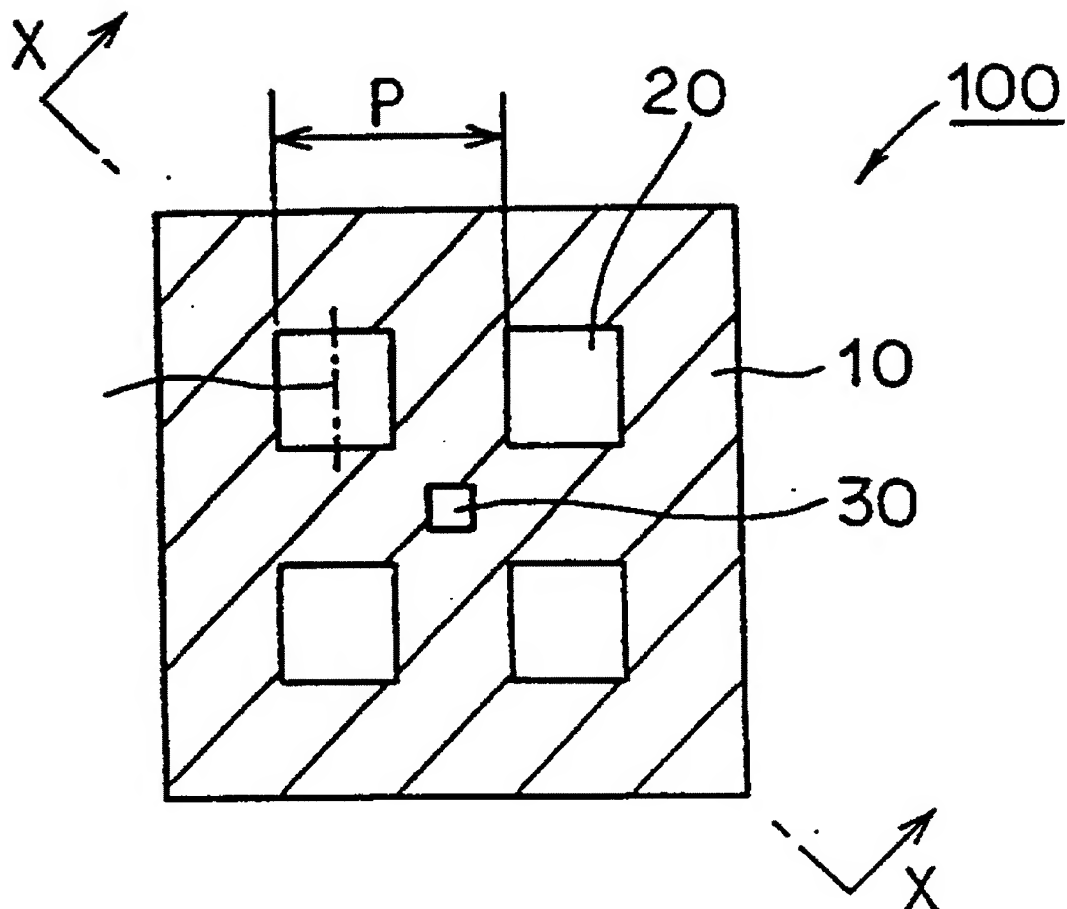
Abstract:

DE 19510564 A

The mask has a first transparent part (10) formed at a predescribed point on a photomask substrate for controlling the transparency and phase of passing exposure light. A second transparent part (20) surrounded by the first, is for releasing a surface of the photomask substrate. An auxiliary pattern (30) is formed in a predescribed region on the first transparent part, near to and around the second transparent part. The auxiliary pattern controls the amount of exposure light on the part corresponding to the region of a material to be exposed.

USE/ADVANTAGE - For use in manufacture of integrated circuits. Prevents production of side leg which would otherwise be produced in the surrounding of pattern by exposure light which passes through mask.

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